

# Electronic Properties of Si Nanowires

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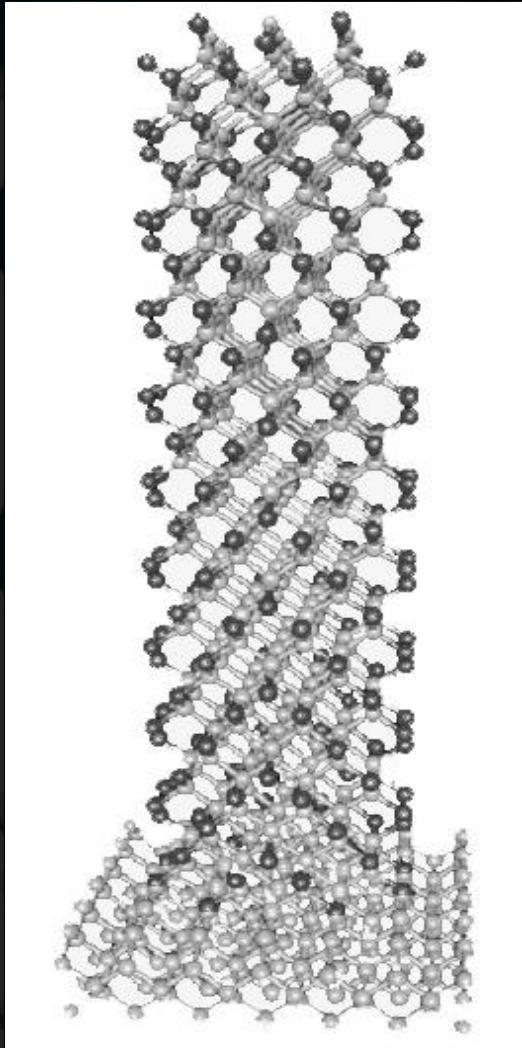
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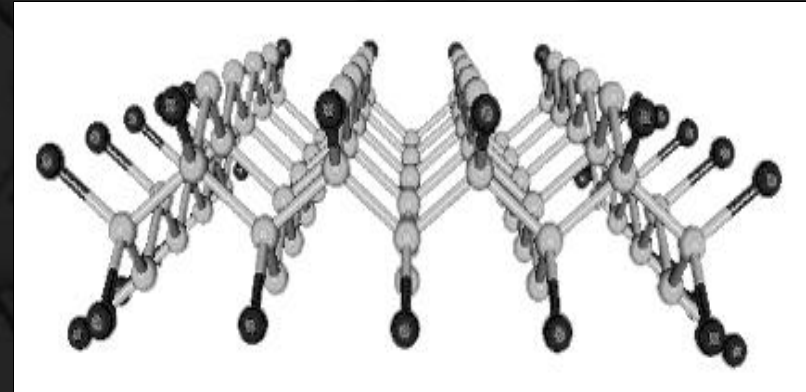
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# Si [100] Nanowire Structure



Si Nanowire on Si substrate



Unit Cell  
H passivated

# Approach

**$sp^3s^*d^5$  empirical tight binding model**

- parameters optimized with genetic algorithm (Boykin et al., Phys. Rev. B, v. 69, 115201 (2004).

**3D discretized effective mass model**

**$E - k_z$  (zeegv)**

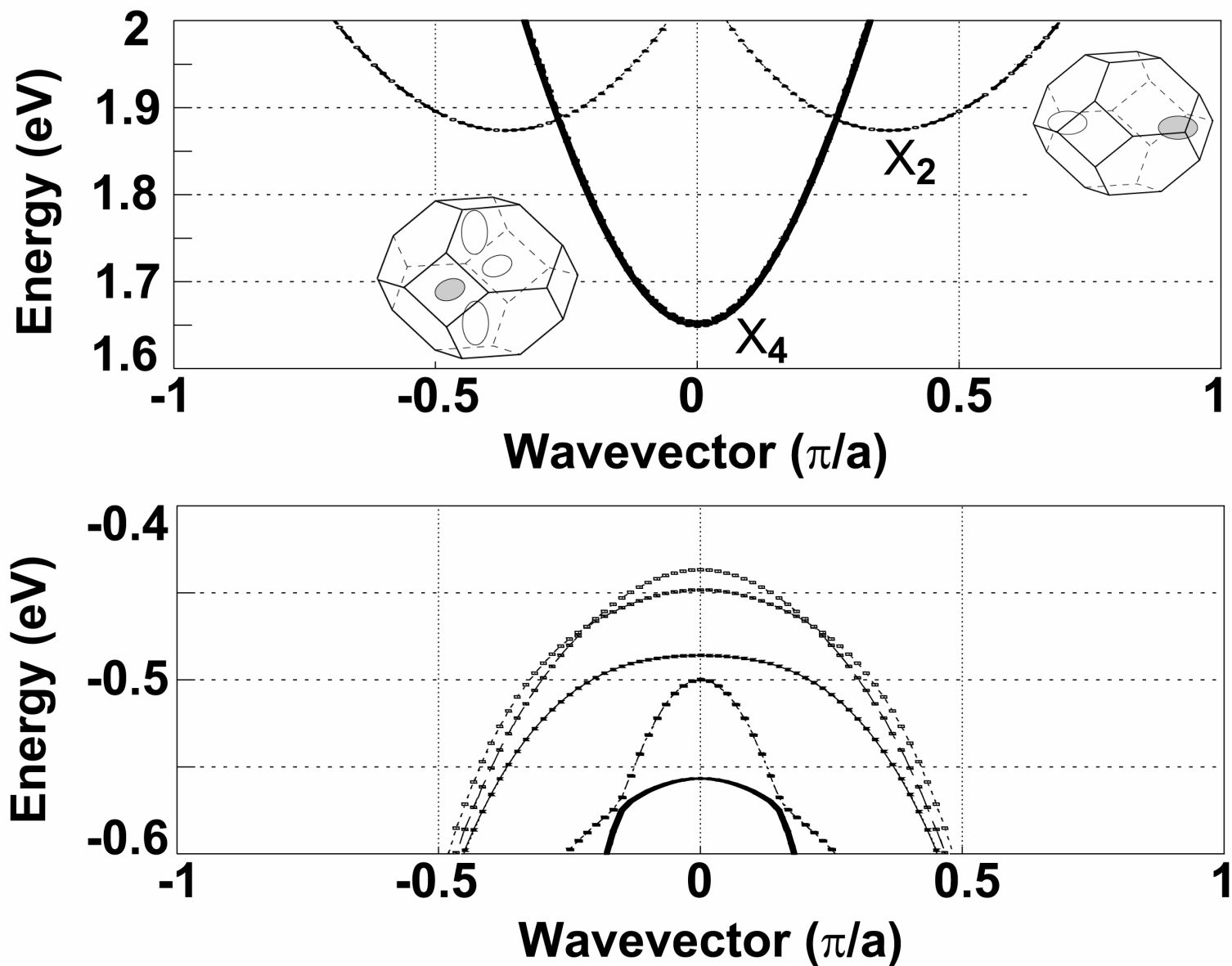
**Transmission vs.  $E$**

- NEGF and RGF  $T = \text{tr}\{G_{1,1}[A_{1,1} - G_{1,1}^R G_{1,1} G_{1,1}^{R\dagger}]\}$

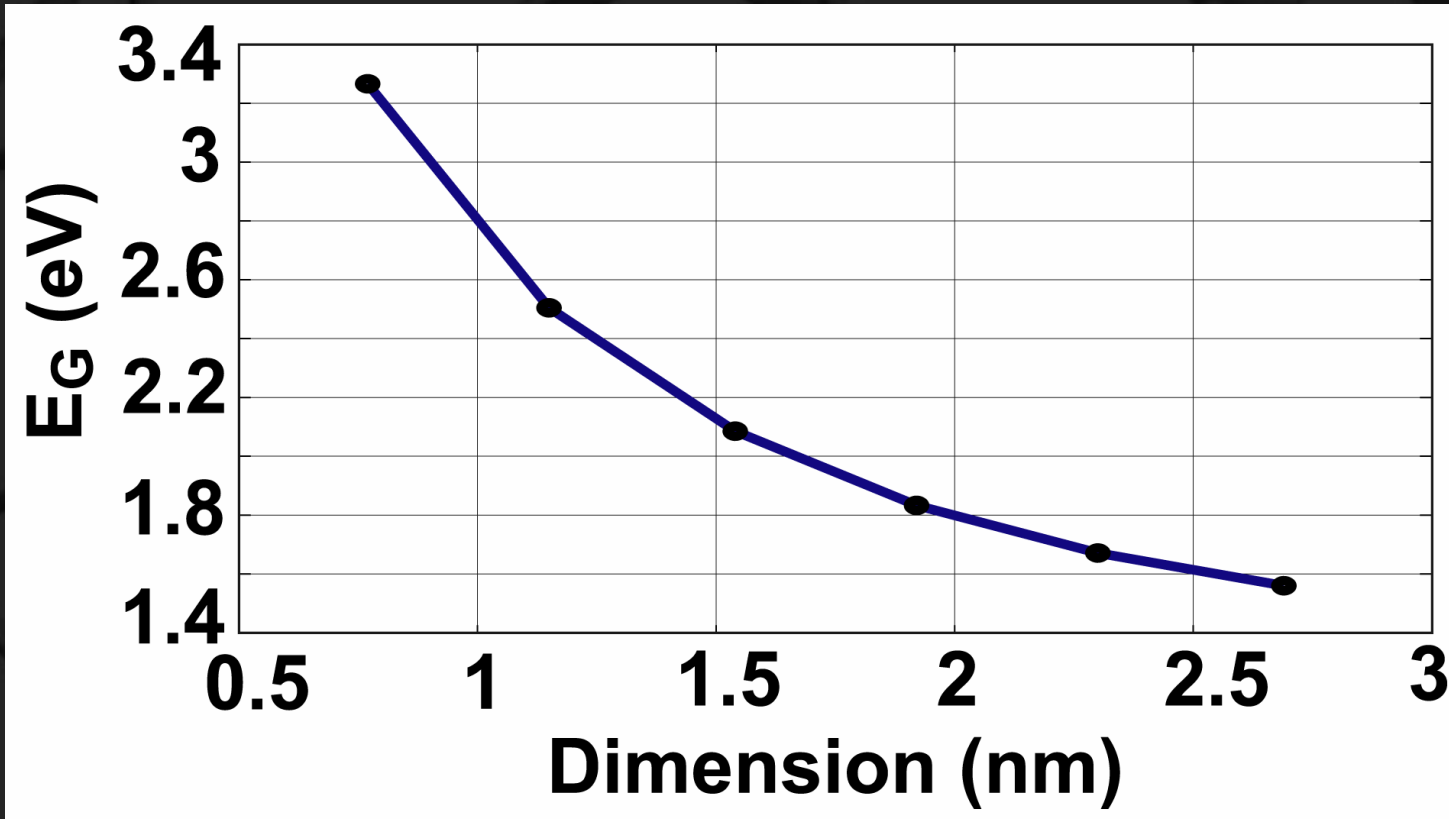
$$g_s^L \leftarrow \dots \dots \dots g_s^R$$
$$g_{i,i}^R = [E - D_i - t_{i,i+1} g_{i+1,i+1}^R t_{i+1,i}]^{-1}$$

$$G_{1,1}^R = [E - D_1 - t_{1,0} g_s^L t_{0,1} - t_{1,2} g_{2,2}^R t_{2,1}]^{-1}$$

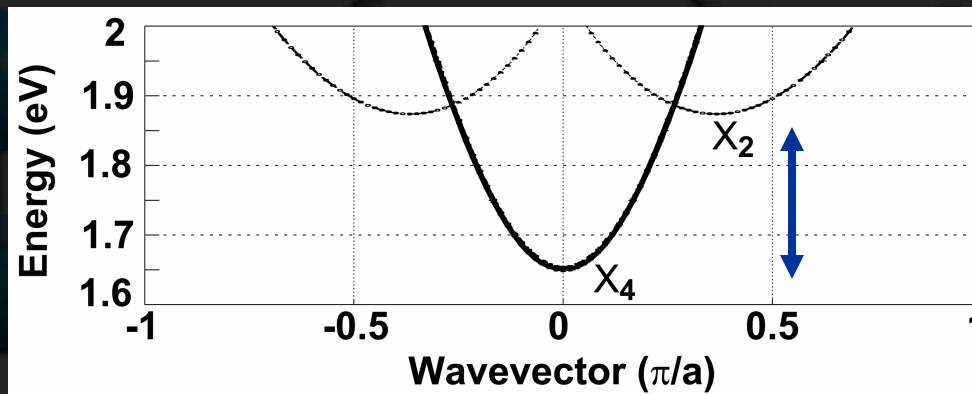
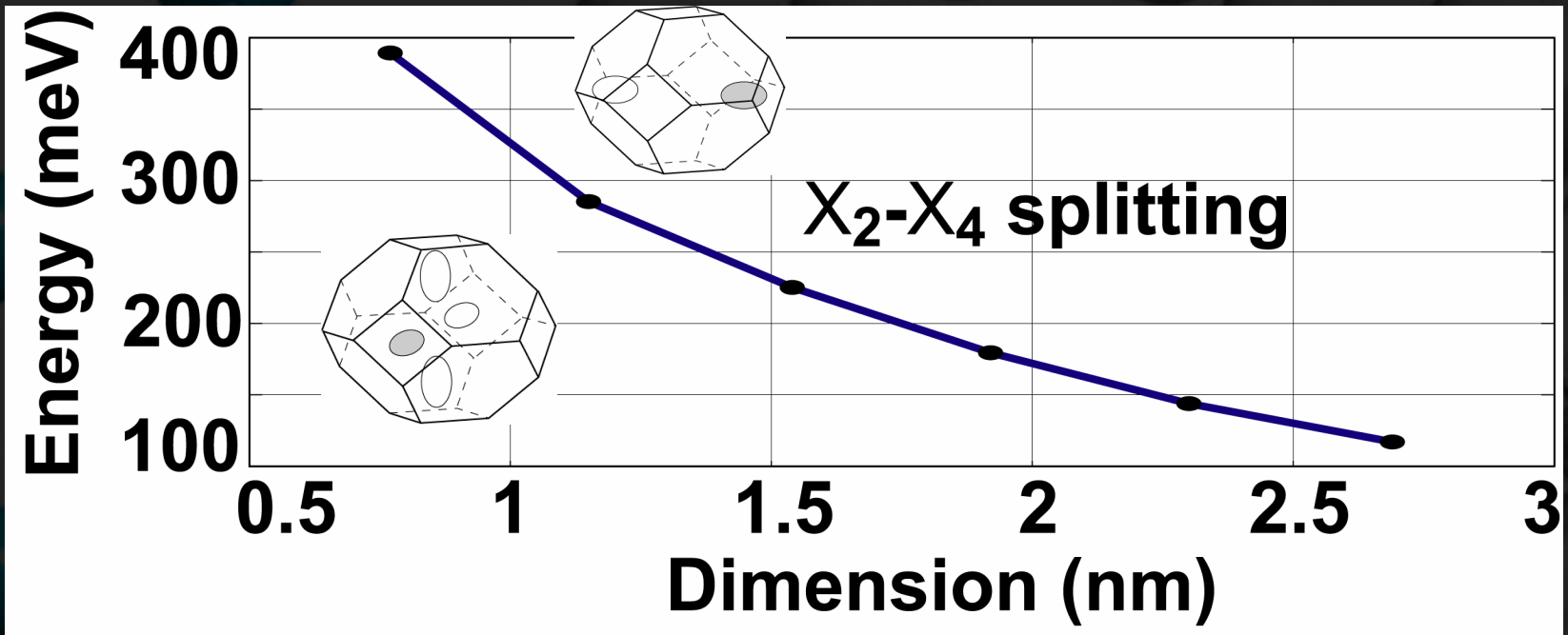
# E- $k_z$ of 1.54 nm Si Wire



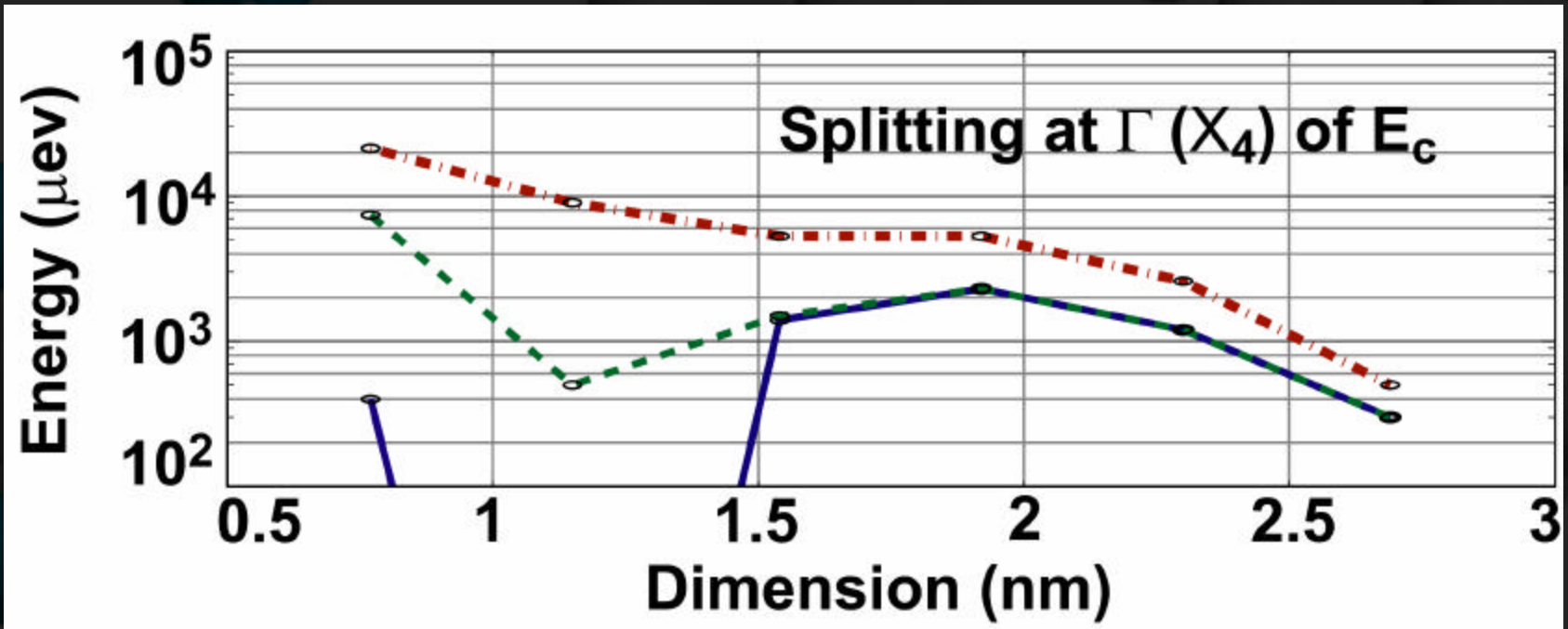
# Band Gap vs. Wire Thickness



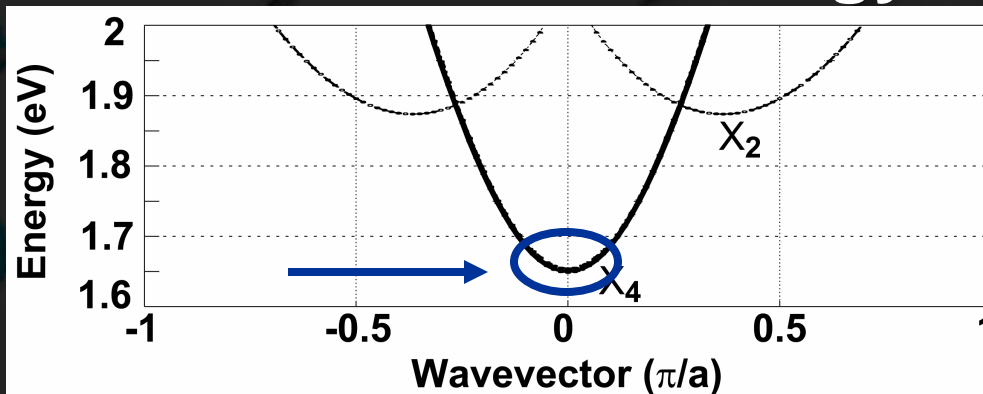
# $X_2 - X_4$ Splitting



# Splitting of $X_4$ States at $\Gamma$

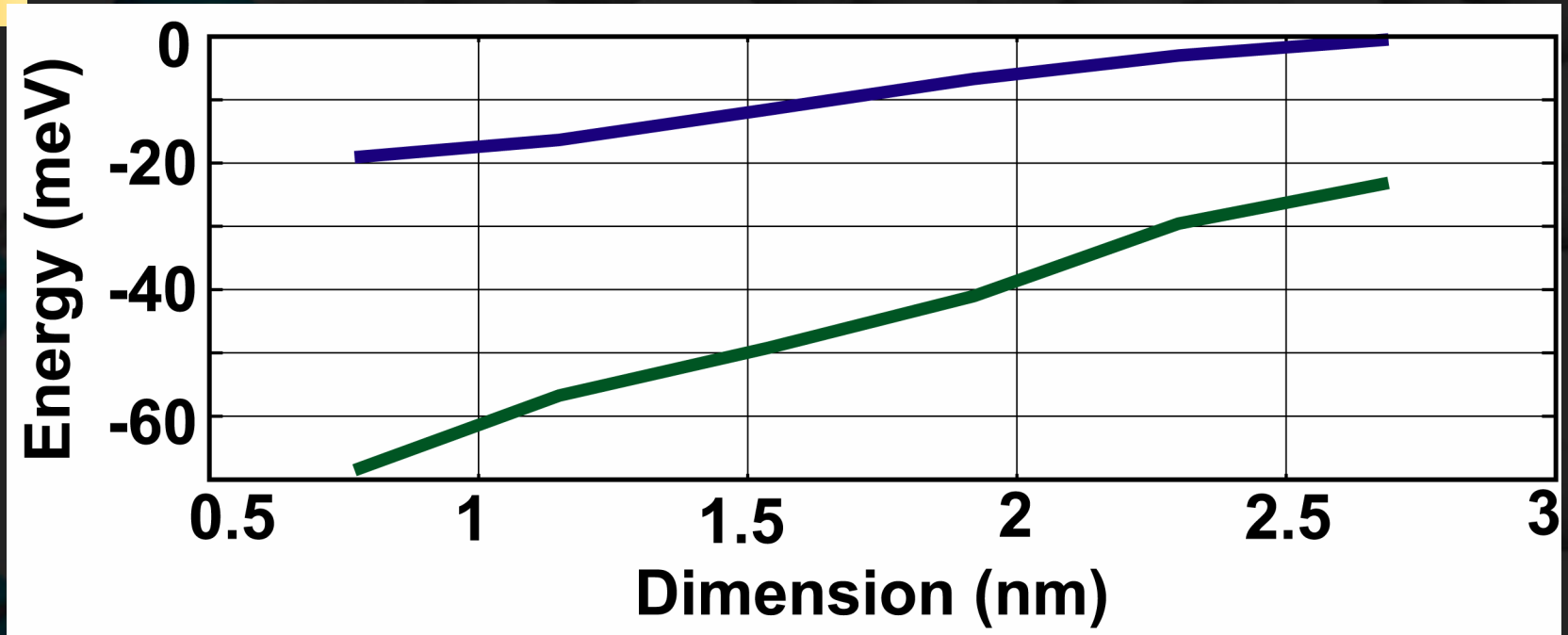


The lowest state is the reference energy  $E=0$  at each dimension.

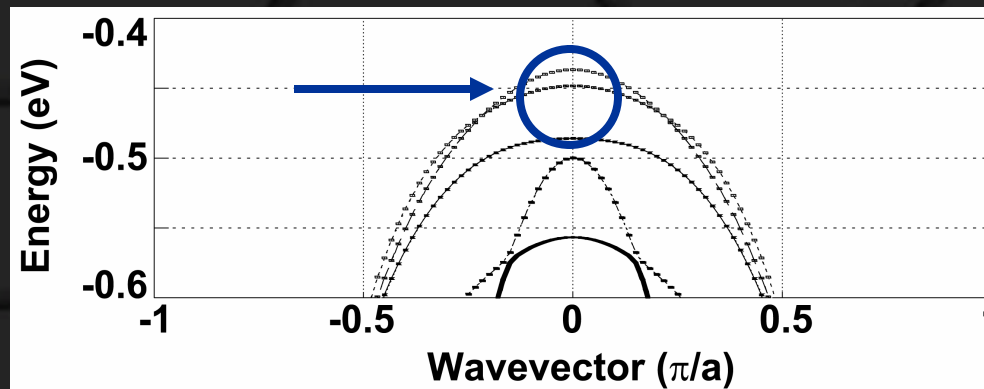




# Splitting of 3 Highest Valence Bands at G

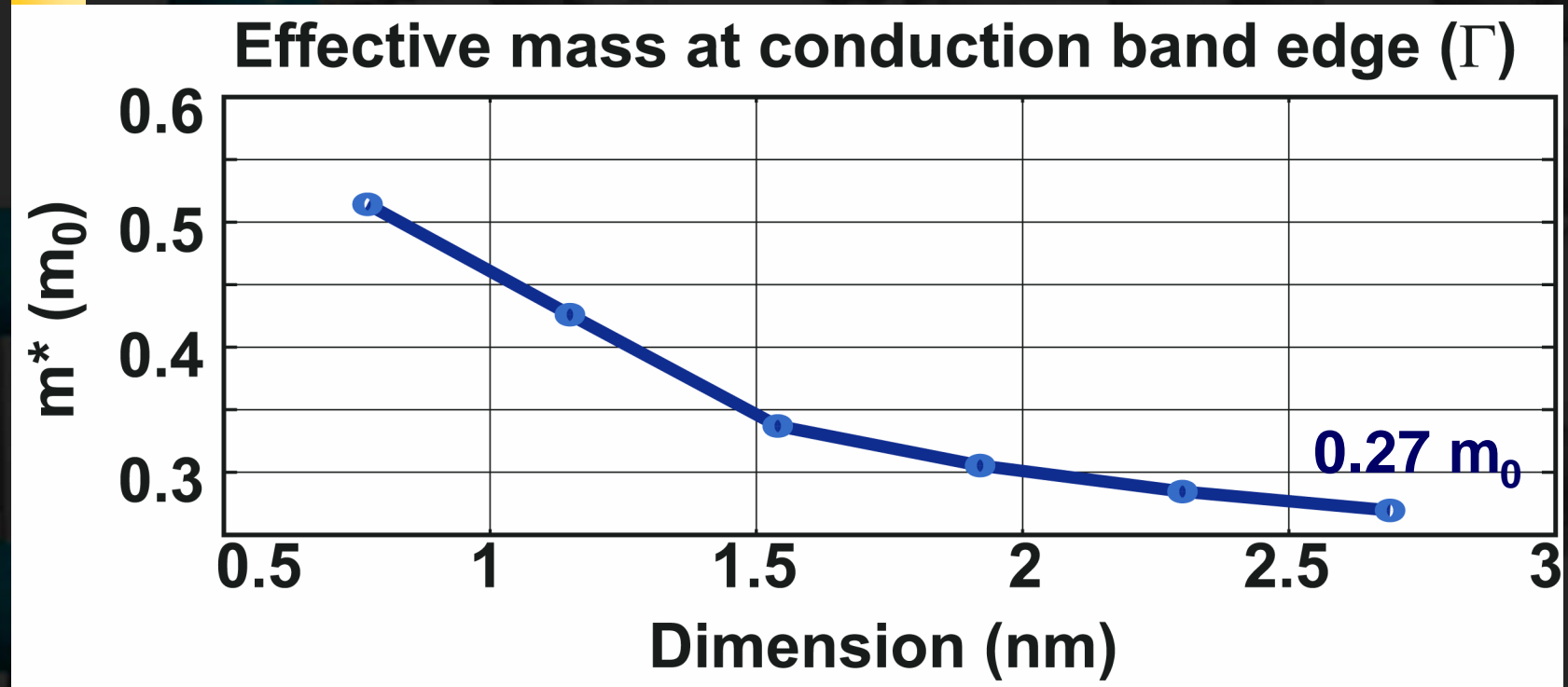


The highest state is the reference energy  $E=0$  at each dimension.

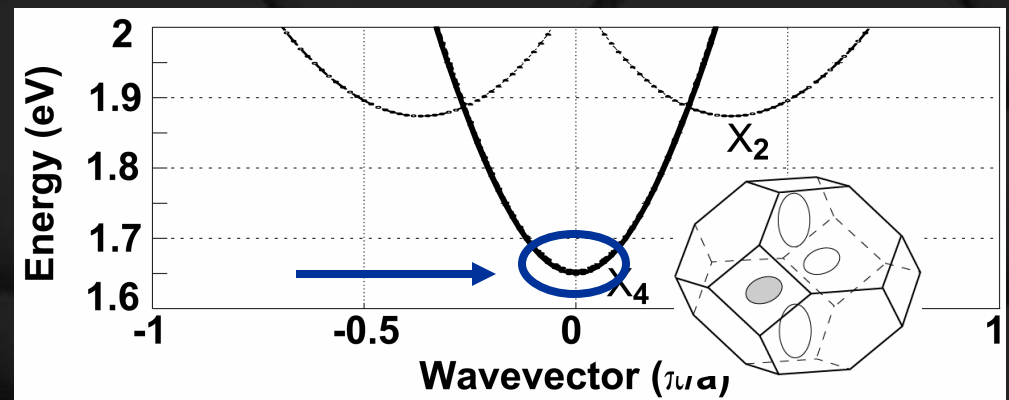




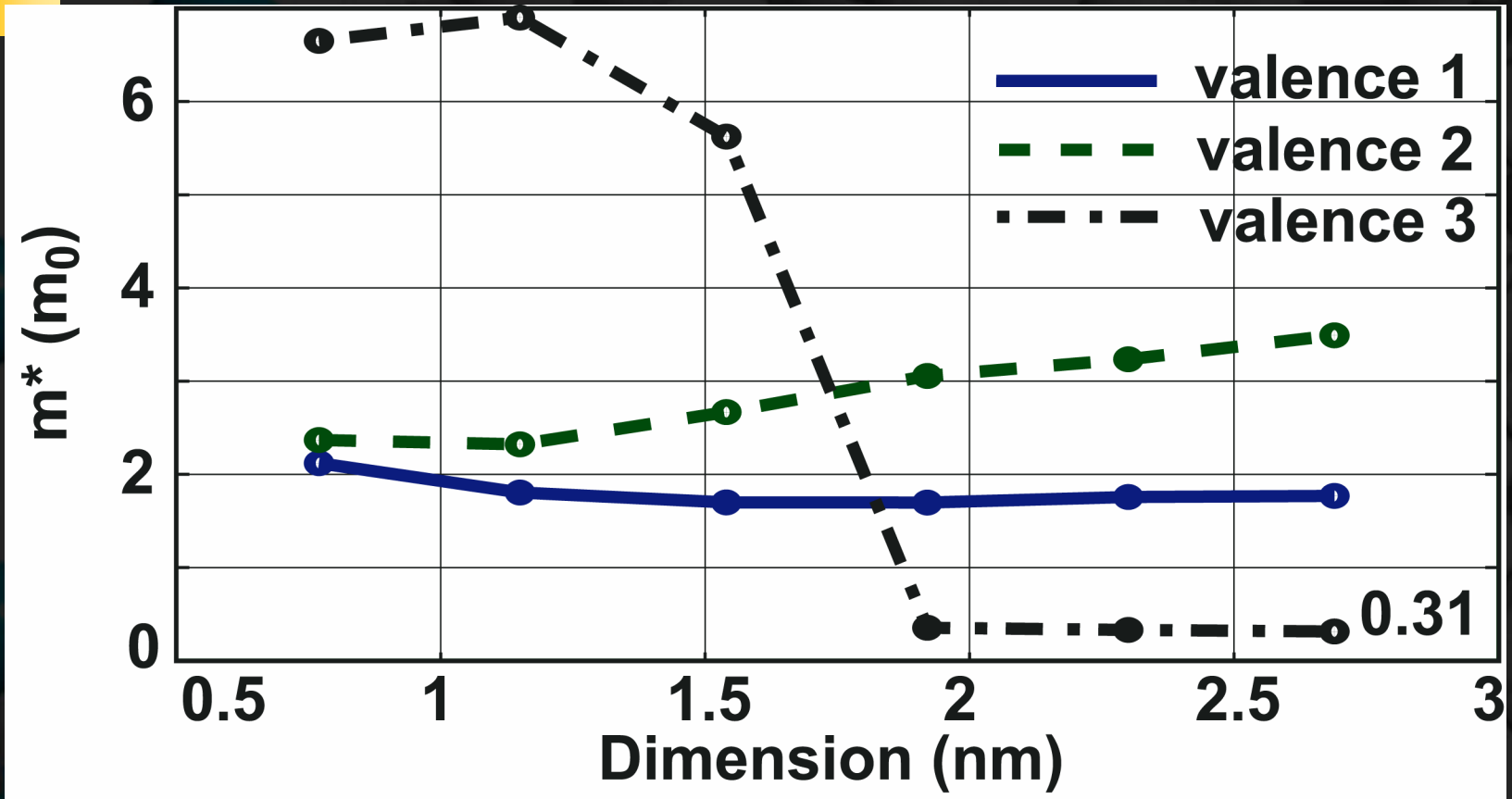
# Effective Mass at Conduction Band Edge



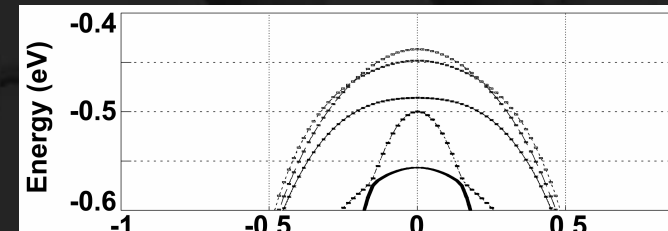
Bulk  $m_t = 0.2 m_0$



# Effective Mass at Valence Band Edge



[100] bulk masses:  $m_{hh} = 0.28 m_0$ ,  $m_{lh} = 0.21 m_0$ , and  $m_{so} = 0.25 m_0$

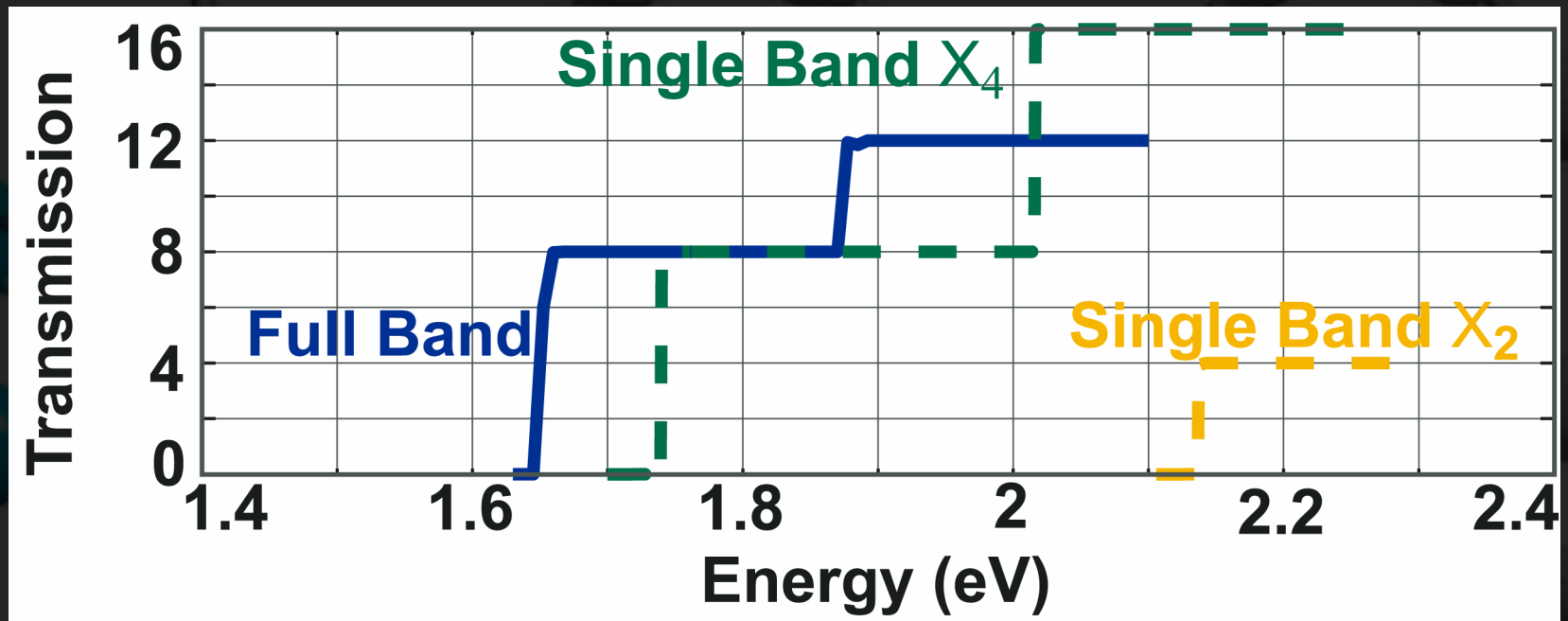
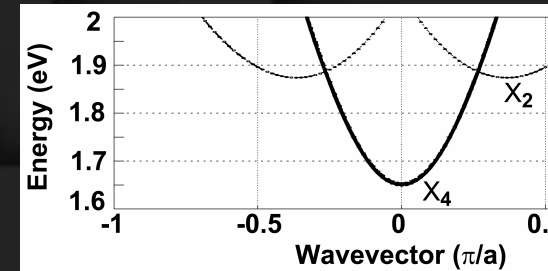


# Conduction Band Transmission: Full Band and Single Band

$$T = \text{tr}\{G_{1,1}[A_{1,1} - G_{1,1}G_{1,1}G_{1,1}]\}$$

1.54 nm Si wire.

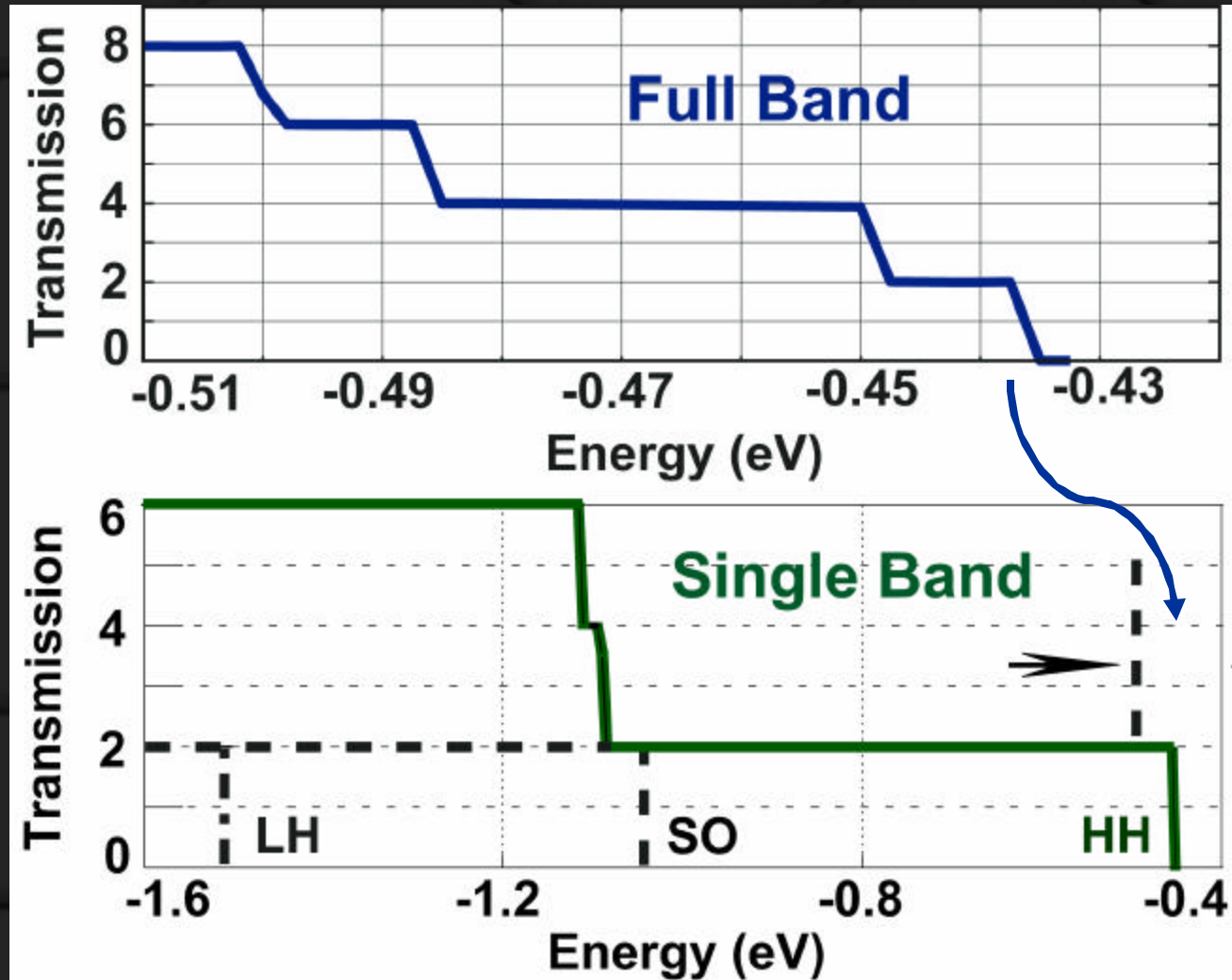
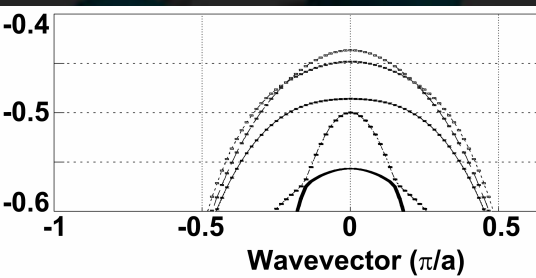
Band edges differ by 100 meV.



# Valence Band Transmission: Full Band and Single Band

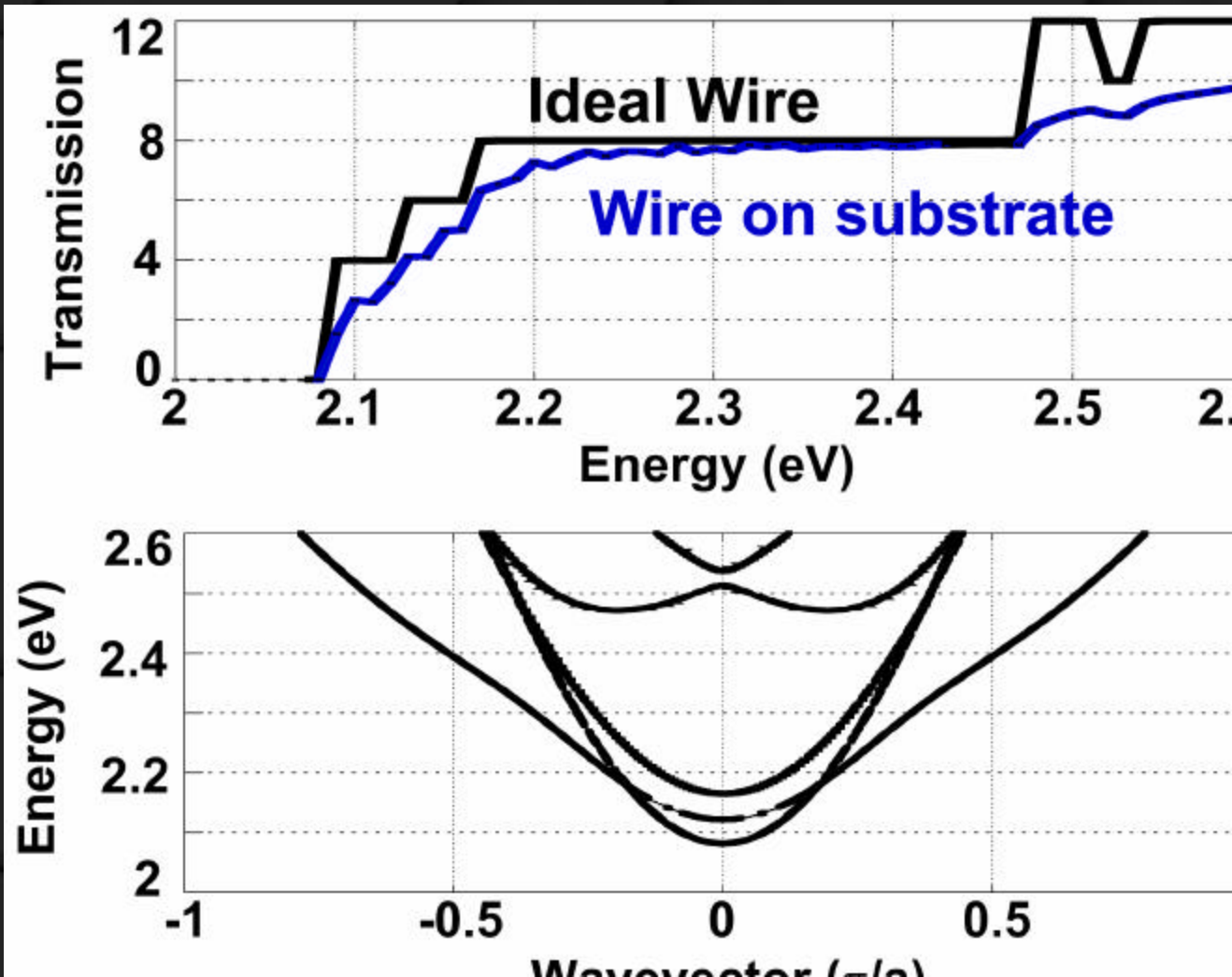
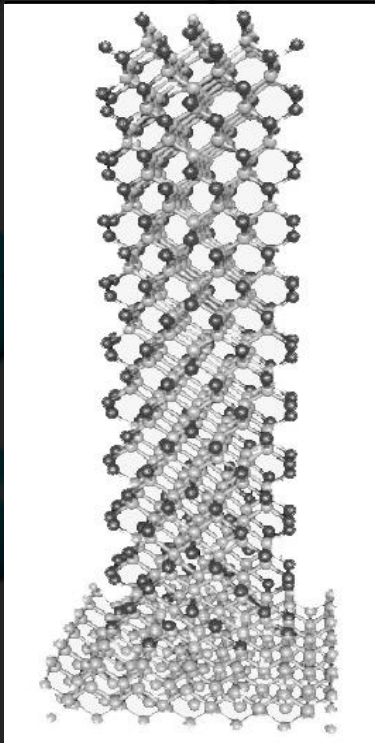
- Band edges differ by 18 meV.

1.54 nm wire



# Transmission of Wire on Si Substrate

$$g_0(\mathbf{R} - \mathbf{R}'; E) = \frac{1}{\Delta^2} \int \frac{d^2 k}{4\pi^2} g_0(\mathbf{k}_{2d}; E) \exp(i\mathbf{k}_{2d} \cdot (\mathbf{R} - \mathbf{R}'))$$



# Conclusion

Brillouin zone  $\frac{1}{2}$  length of bulk Si along D line.

Conduction band: Valley splitting reduces  $m^*$  and confinement increases  $m_t$  of band edge (34% for 2.7nm wire).

$m^*$  of valence band edge 6x heavier than bulk and next highest band even heavier.

For wires  $> 1.54$  nm, conduction band edge splits into 3 energies. Center energy is 2-fold degenerate evenly spaced between lowest and highest energy. Band-edge is non-degenerate.